### Quantitative phase imaging for EUV masks Berkeley UCLA UCSD Stuart Sherwin<sup>a</sup>, Isvar Cordova<sup>b</sup>, Andrew Neureuther<sup>a</sup>, Laura Waller<sup>a</sup>, Patrick Naulleau<sup>b</sup> Workshop a: UC Berkeley; b: Center for X-Ray Optics, LBNL Patterning June 7, 2019



### **Motivation**

- EUV photomasks reflect light with both attenuation and phase delay
- The phase impacts imaging, especially with regard to aberrations (defocus)
- Both the real and imaginary parts of the complex electric field must be known accurately before SMO

### **Objectives**

- Measure the real and imaginary parts of the mask reflection function to the highest possible accuracy
- Explore the potential and limitations of scatterometry vs traditional imaging vs coded-aperture imaging

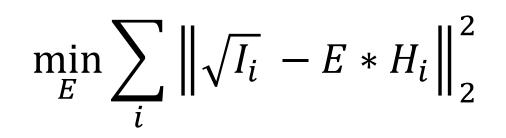
### The Problem

- Optical phase cannot be directly observed, but can be recovered computationally
- We explore several hardware and software solutions for line-space gratings that can be implemented at CXRO

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### **Traditional phase-retrieval**

- Solve for phase from multiple intensity images using nonlinear least-squares
  - Susceptible to error in initial guess



- $I_i$  measured intensity image
- *E* mask's complex field
- $H_i$  Imaging system PSF
- Multiple images w/different  $H_i$  needed

### **Algorithmic improvement: PhaseLift**

- Computationally intensive, but not susceptible to error in initial guess
- Images are *linear* in *rank-1 matrix EE*\*:

$$I_{i} = \operatorname{diag}[F^{*}\operatorname{diag}[\widetilde{H}_{i}]\widetilde{E}\widetilde{E}^{*}\operatorname{diag}[\widetilde{H}_{i}^{*}]F]$$
  
=  $\mathcal{L}_{i}\{\widetilde{E}\widetilde{E}^{*}\} = \mathcal{L}_{i}\{X\}$   
$$\min_{X} \alpha \operatorname{Trace}[X] + \sum_{i} ||I_{i} - \mathcal{L}_{i}\{X\}||_{2}^{2}$$

Small trace promotes Data consistency term low-rank solutions (least-squares)

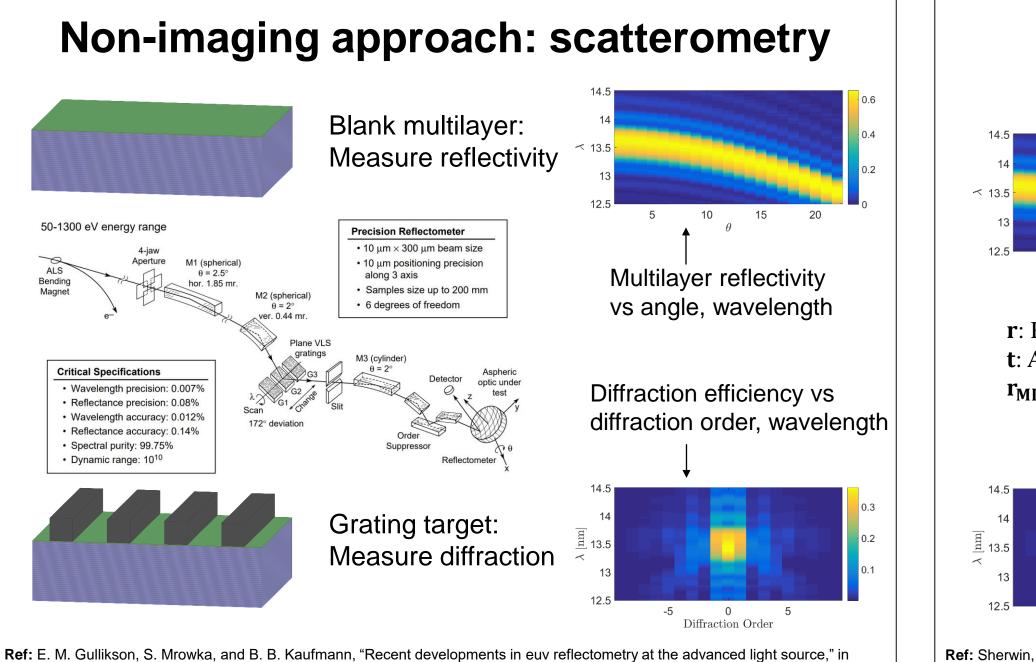
Ref: Candes, E. J., Strohmer, T., & Voroninski, V. (2013). Phaselift: Exact and stable via convex programming. Communications on Pure and Applied Mathematics, 66(8), 1241-1274 Hardware improvement: coded aperture

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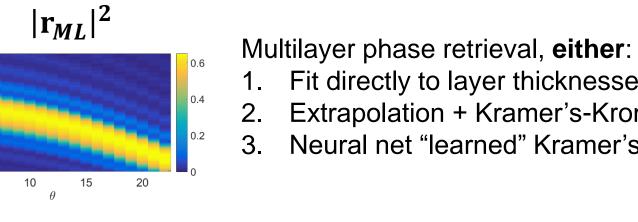
- Self-referencing interferometry:
  - If you can phase-shift only the DC (carrier), phase can be solved directly:

$$I_{\phi_i}[x_j] = (1, \cos \phi_i, \sin \phi_i) \begin{pmatrix} a_{1,j} \\ a_{2,j} \\ a_{3,j} \end{pmatrix}$$
$$a_{2,j} \propto \operatorname{Re}(E[x_j]), a_{3,j} \propto \operatorname{Im}(E[x_j])$$

- Implementation with coded-apertures Insight into coded-aperture design
- microscopy of living cells. Optics express, 17(15), 13080-13094.



# **Scatterometry analysis**

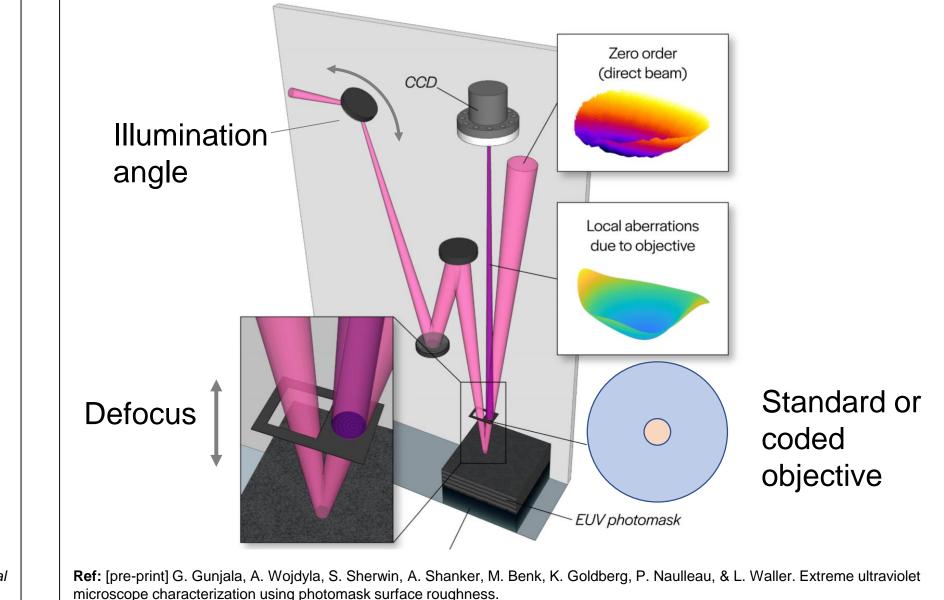


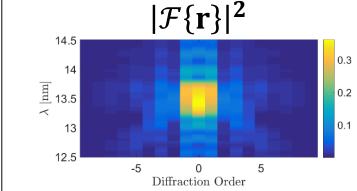
r: Reflected field **t**: Absorber transmission **r**<sub>ML</sub>: Multilayer reflection . Fit directly to layer thicknesses Extrapolation + Kramer's-Kronig

Neural net "learned" Kramer's-Kronig

 $\mathbf{r}[\theta_0] \approx \mathbf{t} \circ \mathcal{F}^{-1}\{\mathbf{\tilde{t}} \circ \mathbf{r}_{\mathbf{ML}}[\theta_0]\}$ 

## SHARP EUV imaging system





Absorber transmission estimation via transmission-reflection-transmission model: regression for t given estimate for  $\mathbf{r}_{ML}$  and measured  $|\mathcal{F}\{\mathbf{r}\}|^2$ 

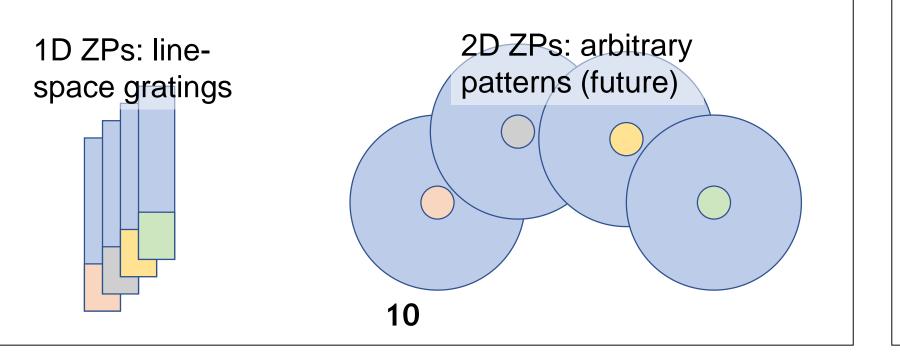
Ref: Sherwin, S., Neureuther, A., & Naulleau, P. (2018, October). EUV mask characterization with actinic scatterometry. In International Conference on Extreme Ultraviolet Lithography 2018 (Vol. 10809, p. 108090T). International Society for Optics and Photonics.

**Coded aperture: phase-shifting DC** 

- SHARP: custom zone-plate (ZP) objectives
- Set of coded ZPs for phase retrieval

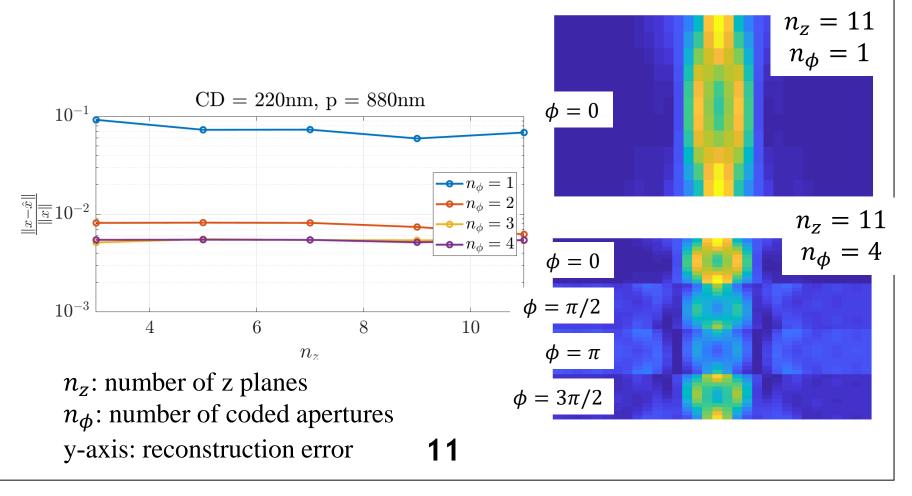
Emerging Lithographic Technologies V, 4343, pp. 363–374, International Society for Optics and Photonics, 2001.

0 order passes through phase-shifted region, scattered light imaged normally



## Initial studies using PhaseLift

Key result: coded aperture improves accuracy over defocus for larger pitch



## **Future Goals**

- Fabricate set of DC phase-shifted • zone-plates
  - 1D, 2 orientations for H/V features
- Conduct experiments at ALS using  $\bullet$ measurement modalities discussed

#### Acknowledgment

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